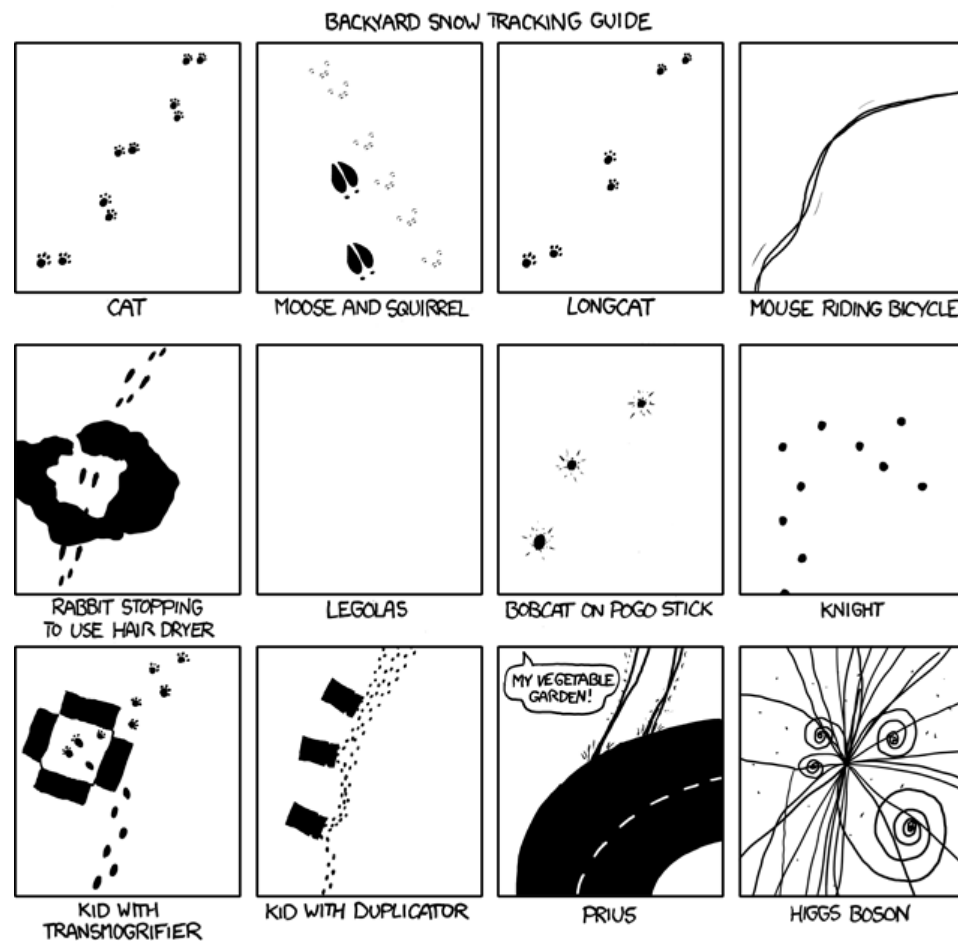
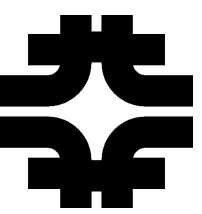




# Making Tracks at DØ



Satish Desai – Fermilab



# What Does a Tracker Do?



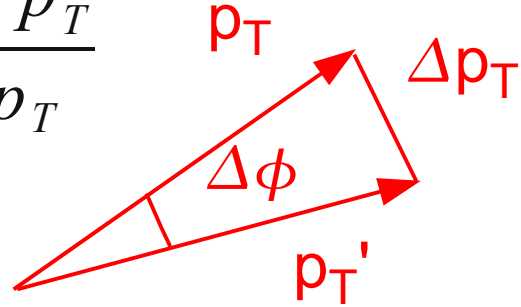
- It finds tracks (well, duh!)
    - Particle ID ( $e/\gamma$  separation, b-tagging...)
  - Measurements of
    - Momentum
    - Electric Charge
    - Impact Parameters
    - Position and Trajectory
- really measuring curvature/charge



# Measuring Momentum

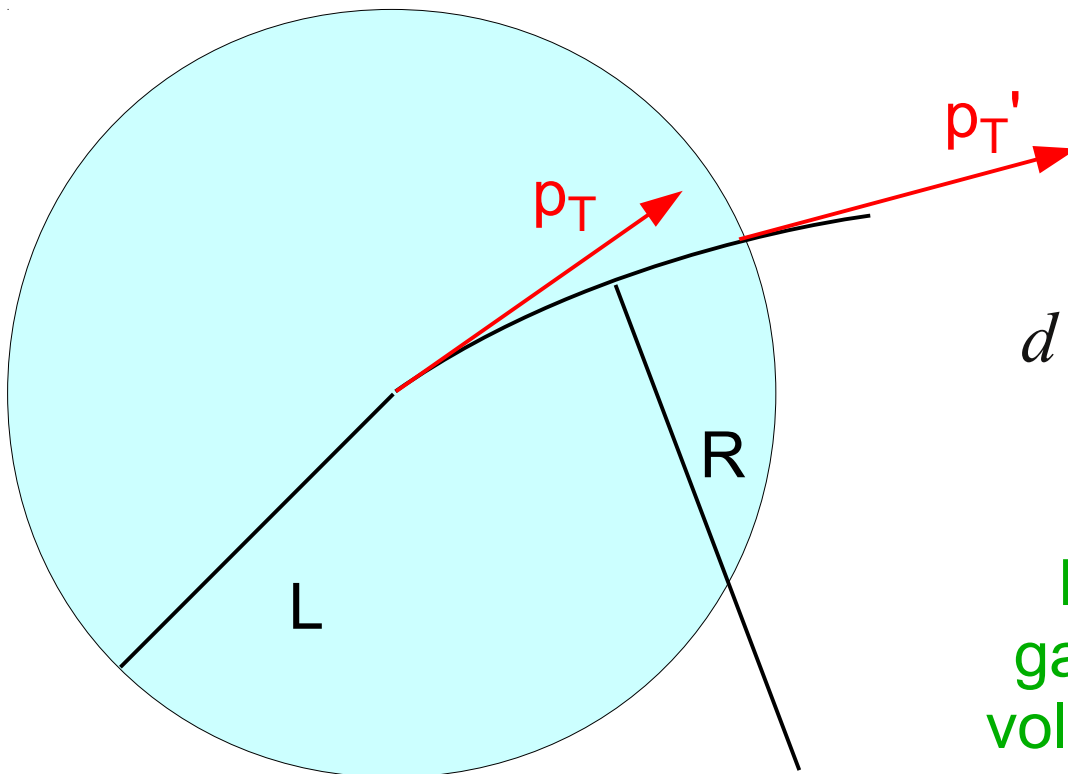
$$\frac{L}{R} = \Delta\phi = \frac{\Delta p_T}{p_T}$$

$$p_T = qBR$$



	B (Tesla)	L (cm)
DØ	2	52
CDF	1.4	140

$$\frac{1}{p_T} = \frac{\Delta\phi}{qBL}$$



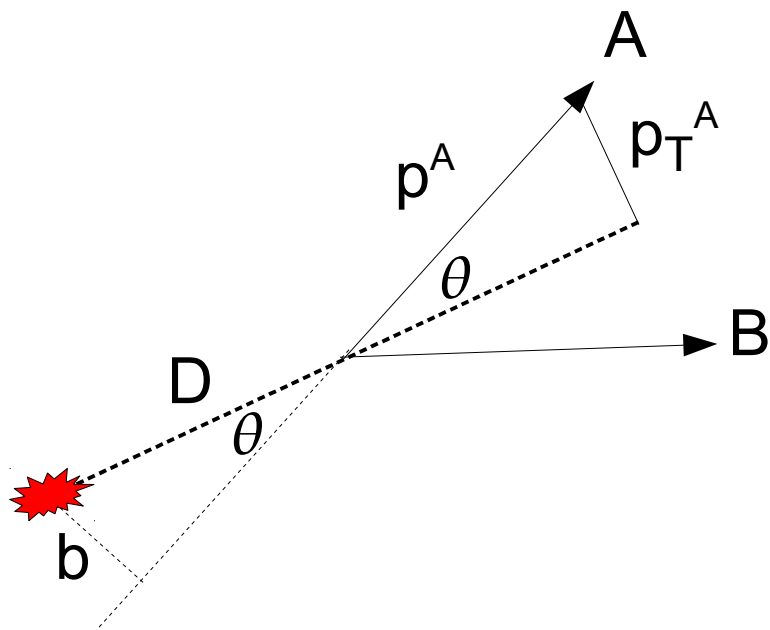
Spatial resolution of  
outermost tracking layer

$$d\left(\frac{1}{p_T}\right) = \frac{\Delta\phi}{qBL^2} ds$$

Momentum resolution  
gains more from tracking  
volume than magnetic field



# Impact Parameters



$$b = D \sin \theta = D \frac{p_T^A}{p^A}$$

Assume massless decay products...

$$D = \gamma_D c \tau_D \quad \sin \theta = \frac{1}{\gamma_D}$$

Impact parameter independent of boost!

- Impact parameter measurements for b-tagging, flavor physics, lepton ID...
- IP resolution driven by hit resolution
- Get hits close to original collision

	$c\tau$ ( $\mu\text{m}$ )
$D^\pm$	312
$D^0$	123
$B^\pm$	491
$B^0$	457



# Detector Technologies



- Bubble chambers:

- Very good resolution
- Way too slow for colliders

- Scintillators

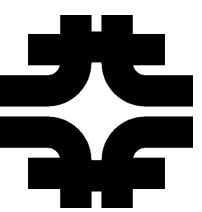
- High material budget
- Speed  $O(10 \text{ ns})$
- Resolution  $O(100 \mu\text{m})$

- Drift chambers/tubes

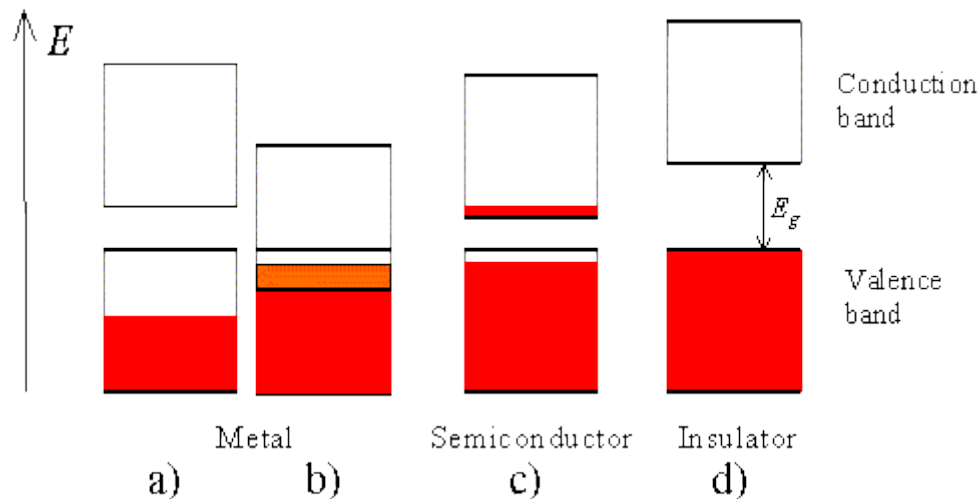
- Low material budget
- Speed  $O(100 \text{ ns})$
- Resolution  $> 100 \mu\text{m}$

- Silicon

- High material budget
- Speed  $O(10 \text{ ns})$
- Resolution  $O(10 \mu\text{m})$



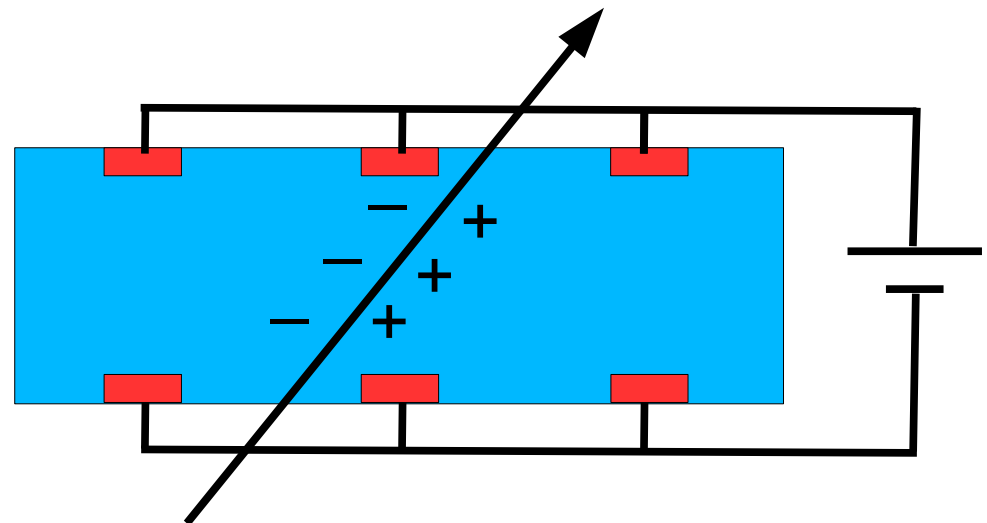
# Silicon Detectors



Source: <http://ecee.colorado.edu/~bart/book>

- Drift time  $\sim 7\text{ns}$
- Depends on voltage and sensor thickness
- Resolution depends on strip spacing

- Band gap is 1.12 eV for Silicon
- Really 3.6 eV needed for ionization (heating)
- MIP deposits 79 keV
- 22k electrons, 3.5 fC



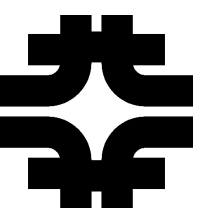
MIP = Minimum Ionizing Particle



# A Problem

---

- Signal size is 22k electrons
- Charge carrier density in conduction band:  $10^{11}/\text{cm}^3$
- Typical sensor dimensions
  - 300  $\mu\text{m}$  thick
  - 6 cm long
  - 50  $\mu\text{m}$  strip spacing (more relevant than width)



# A Problem

- Signal size is 32k electrons
- Charge carrier density in conduction band:  $10^{11}/\text{cm}^3$
- Typical sensor dimensions
  - 300  $\mu\text{m}$  thick
  - 6 cm long
  - 50  $\mu\text{m}$  strip spacing (more relevant than width)
- $10^8$  background charge carriers in neighborhood of signal
- Electron-hole pairs recombine easily

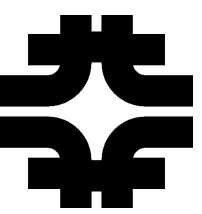




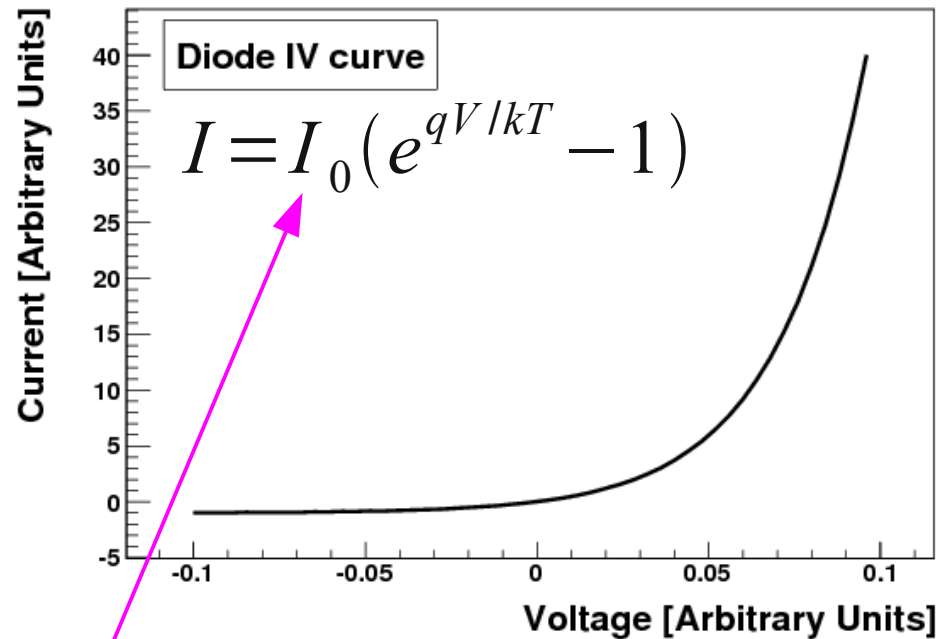
# A Problem

- Signal size is 32k electrons
- Charge carrier density in conduction band:  $10^{11}/\text{cm}^3$
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  - 300  $\mu\text{m}$  thick
  - 6 cm long
  - 50  $\mu\text{m}$  strip spacing (length more relevant than width)
- $10^8$  background charge carriers in neighborhood of signal
- Electron-hole pairs recombine easily

Disaster!!

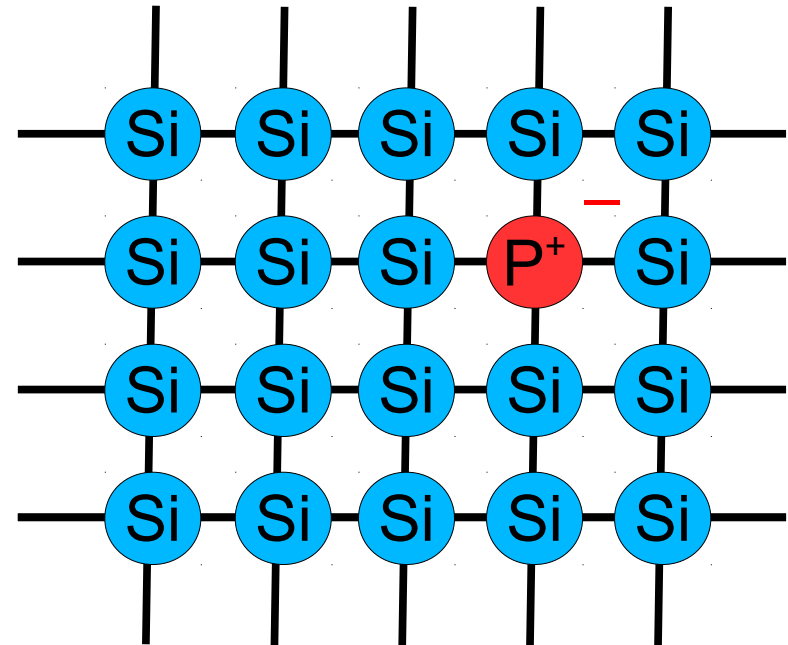


# Behold, the Power of Diodes



O (10 nA), depends on temperature, doping

n-type semiconductor



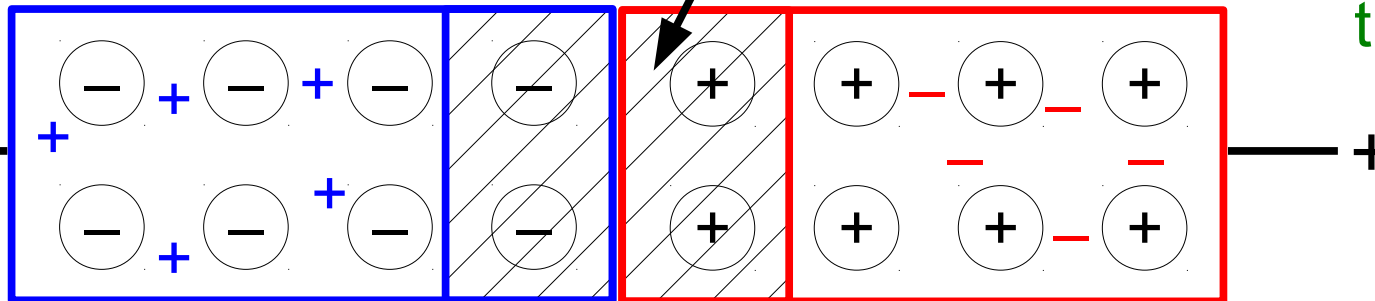
Depletion Region

p-type

n-type

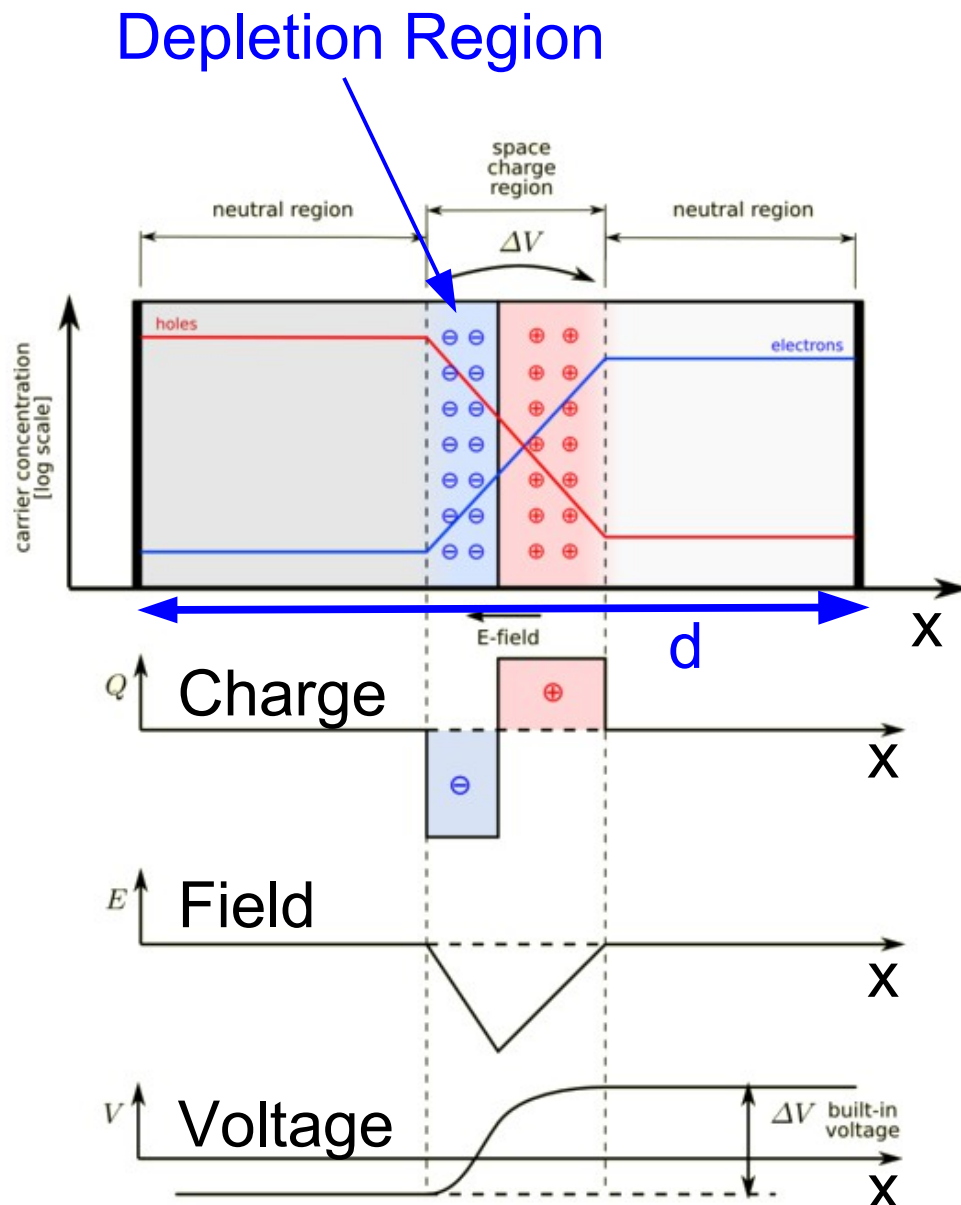
Charge fixed to lattice fights the external voltage

Reverse bias





# Depletion Voltage



$$\frac{-d^2 V}{dx^2} = \frac{dE}{dx} = \frac{q N_{eff}}{\epsilon \epsilon_0}$$

- Voltages and fields from Poisson's equation
- **Charge density:**
  - Set by doping concentration ( $N_{eff}$ )
  - Zero outside depletion region
- p-side very thin, heavily doped
- Need full depletion for full efficiency

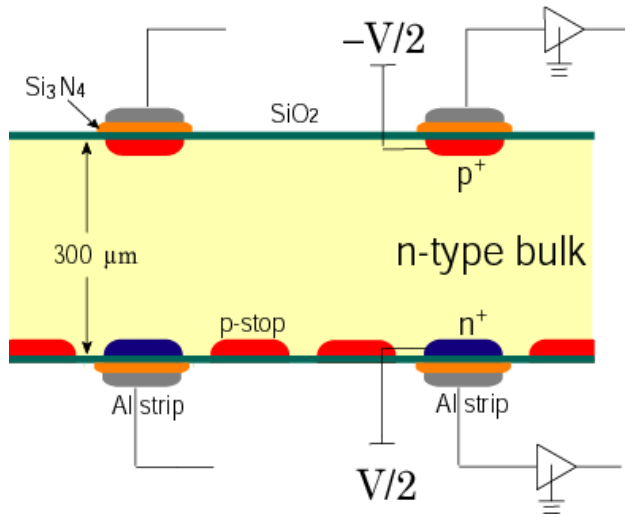
$$V_{depl} = \frac{q_0}{2 \epsilon \epsilon_0} |N_{eff}| d^2$$



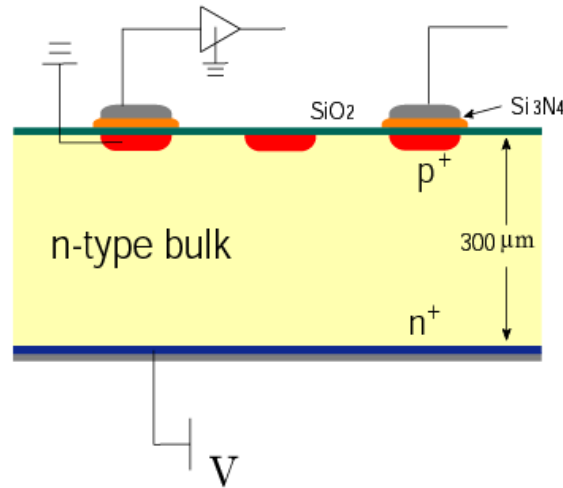
# Closer to Reality



Double-Sided Sensor

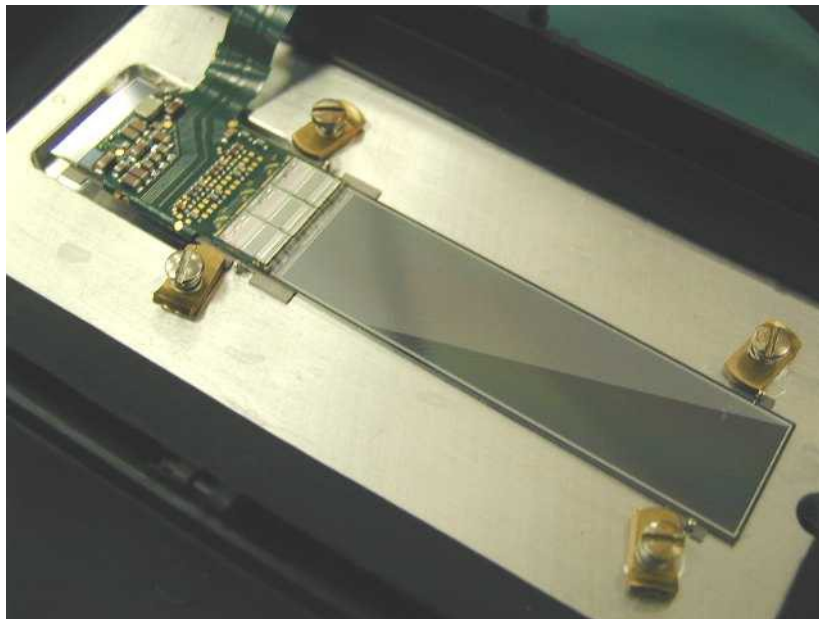
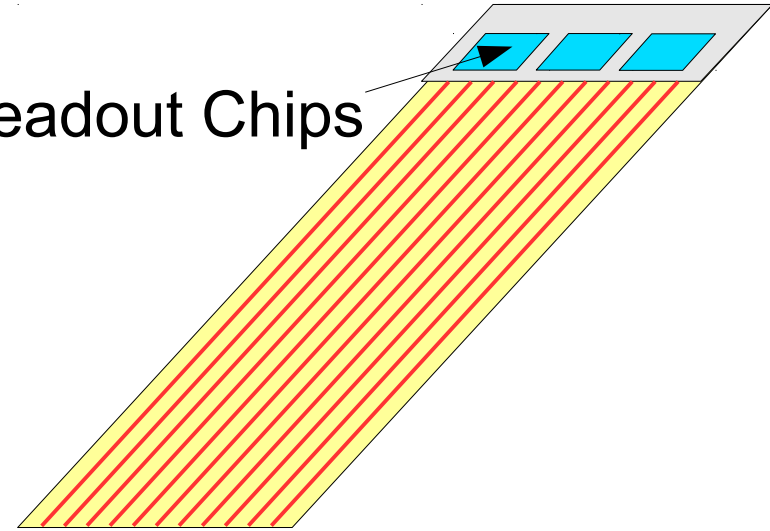


Single-Sided Sensor



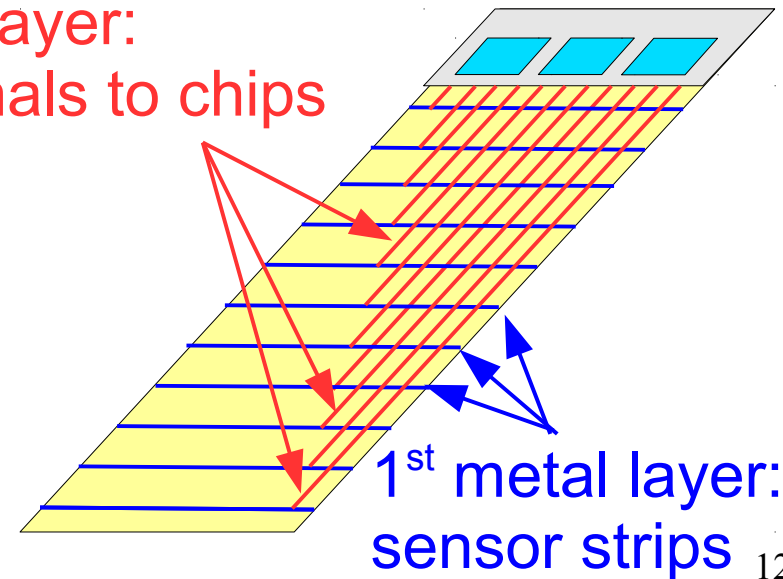
Single Sided

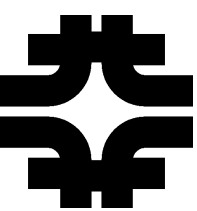
Readout Chips



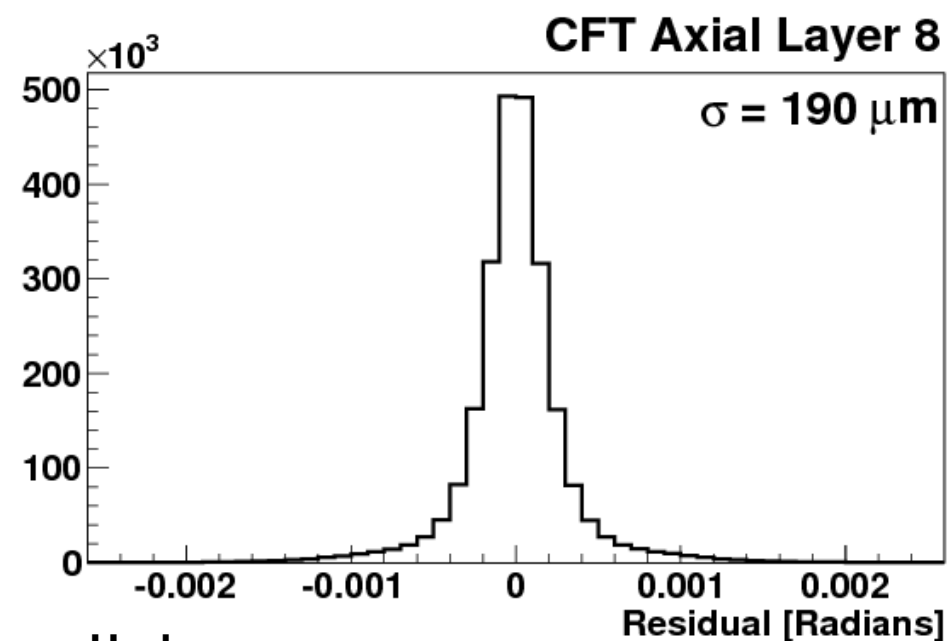
Double-sided Double-Metal

2<sup>nd</sup> metal layer:  
bring signals to chips

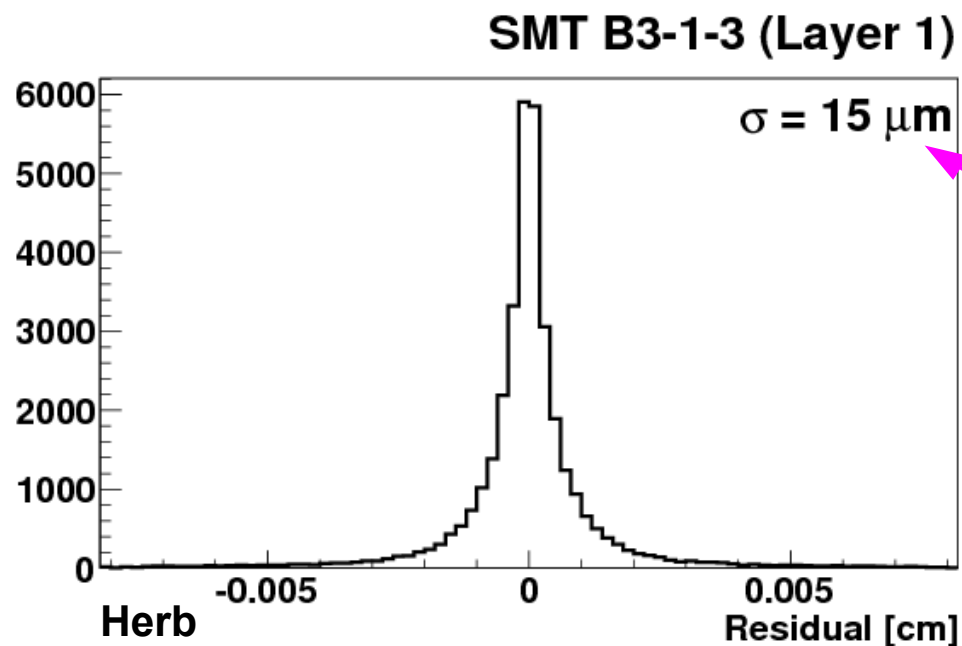
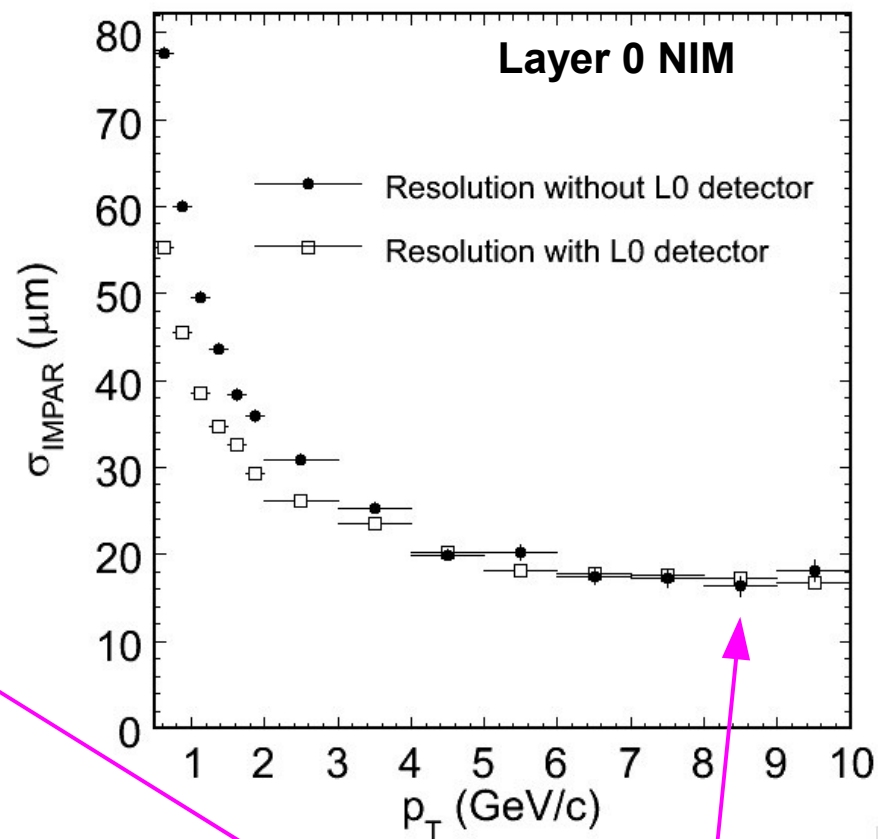




# Performance



IP resolution degraded  
by multiple scattering



Compare to B/D  
 $c\tau = O(100 \mu\text{m})$



# Radiation Damage



## Bulk Damage

- Ionization effects not important
- Non-ionizing: atoms knocked out of lattice
- Effectively induces p-type doping
- Changes depletion voltage

## Surface Damage

- Charge trapping in insulating layer
- Increases in leakage current
- Large electric fields near surface
- Breakdowns at high voltage



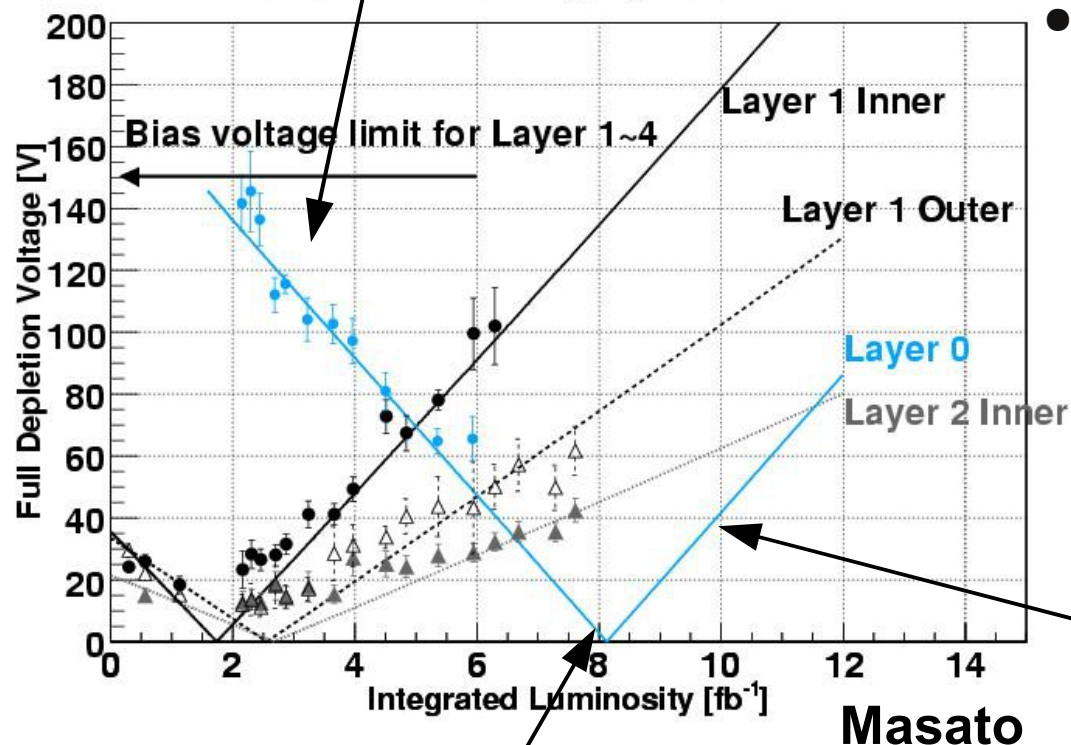


# Signs of Aging



n-type semiconductor  
 $|N_{\text{eff}}|$  decreasing

DØ Silicon Detector Radiation Aging Status as of Jan. 2010



type inversion

$$V_{\text{depl}} = \frac{q_0}{2\epsilon\epsilon_0} |N_{\text{eff}}| d^2$$

- If applied voltage too high ( $\sim 150$  V):

- Noise increases dramatically (microdischarge)
- Coupling capacitors breakdown (non-recoverable)

p-type semiconductor  
 $|N_{\text{eff}}|$  increasing

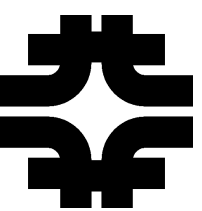


# Summary



- Tracking detectors are an important component of collider experiments
- Semiconductor devices satisfy key requirements of speed and precision
- Reverse biased diode configurations make signal to noise ratio manageable
- Lifetime of silicon detectors limited by radiation induced effects
  - Microdischarge
  - Changes in depletion voltage

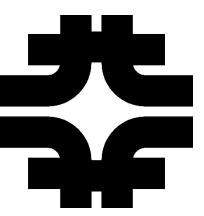




# For Further Information



- *The Physics of Particle Detectors*, Dan Green
- *Semiconductor Radiation Detectors*, Gerhard Lutz
- *Silicon Particle Detectors - Why they are useful and how they work*, William Trischuk
- *Depletion Voltage for the DØ Silicon Microstrip Tracker Using the n-side Noise Method*, DØ Note 4917 (S. Burdin and S. Lager)
- *Radiation Damage in Silicon Particle Detectors*, M Moll, PhD Thesis

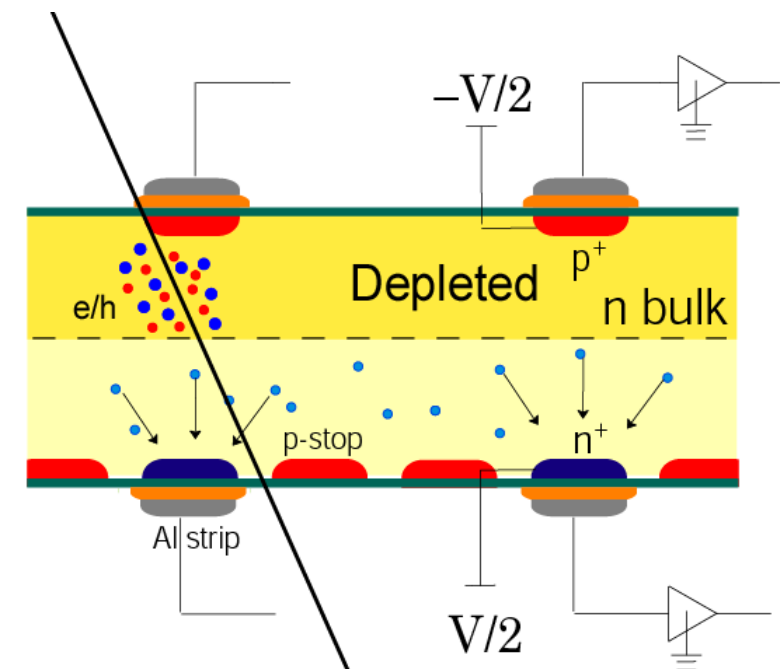


# Backup Slides

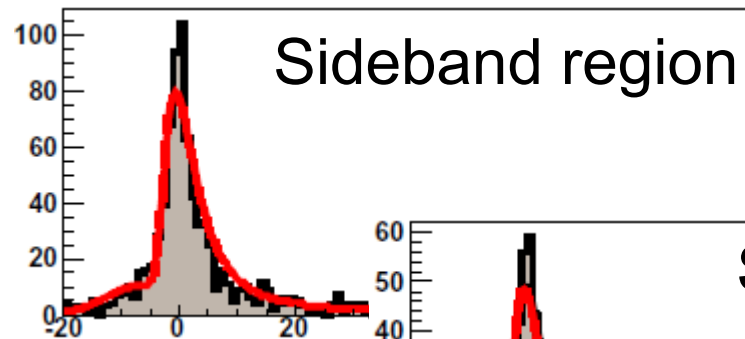
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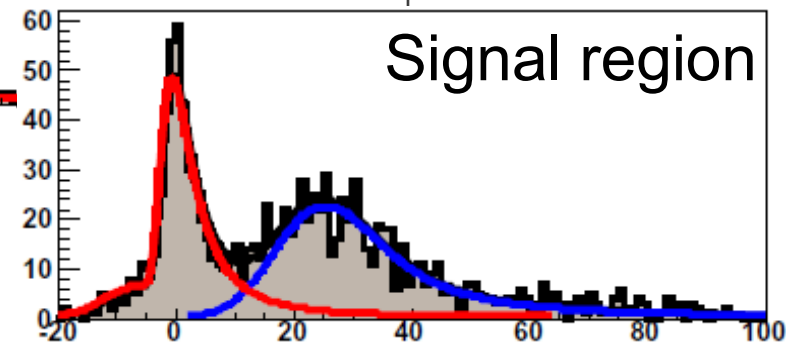
# Measuring Depletion Voltage



Determine depletion voltage by looking at signal size vs applied voltage

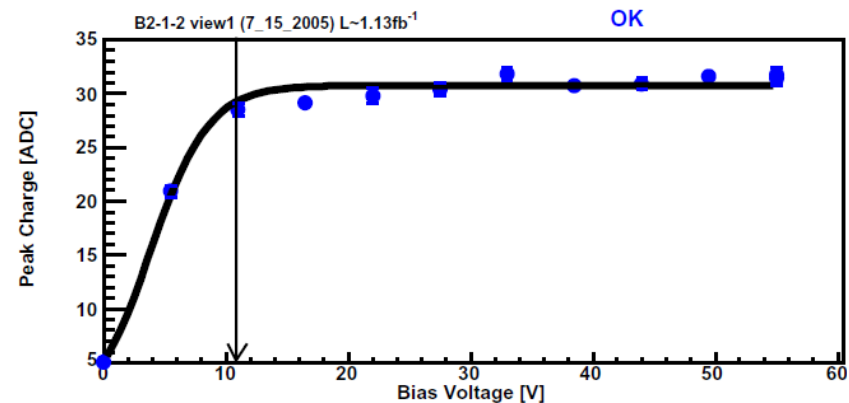
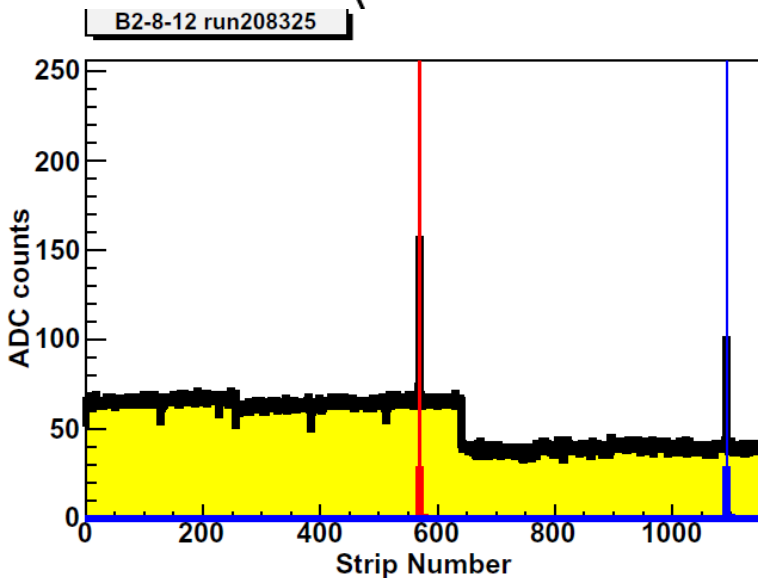


Sideband region

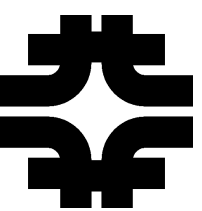


Signal region

Can also look at noise levels



Plots stolen from Masato

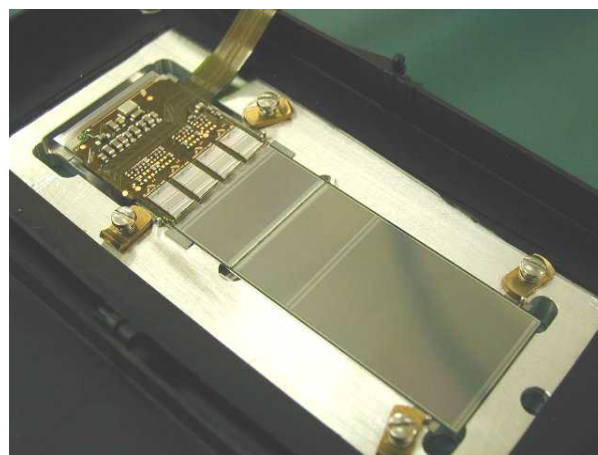
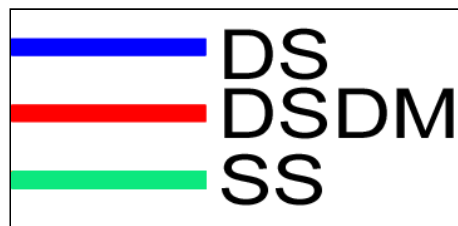
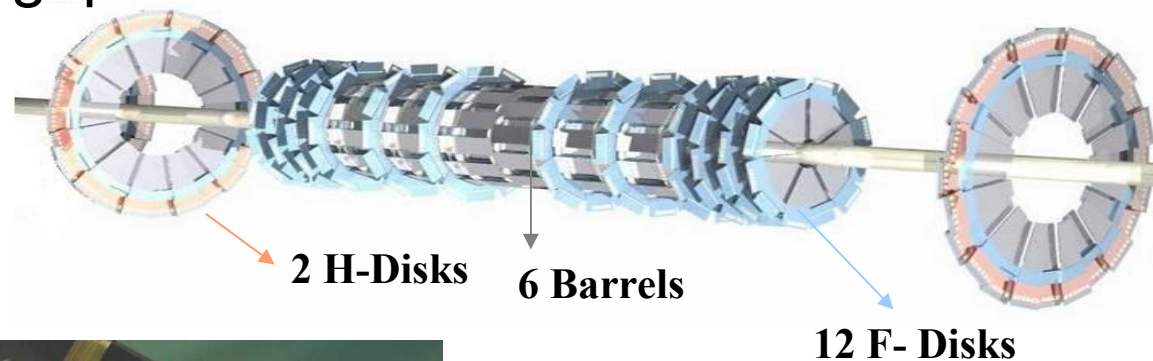


# The DØ Silicon Tracker

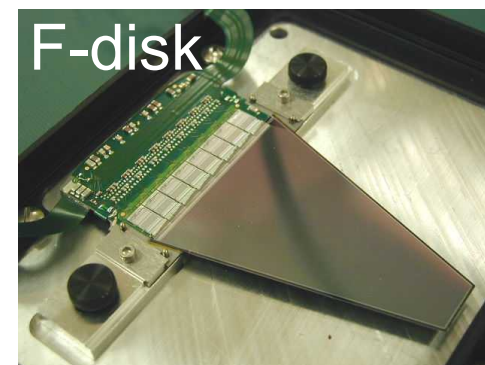


Staggered sublayers to avoid  $\phi$  gaps

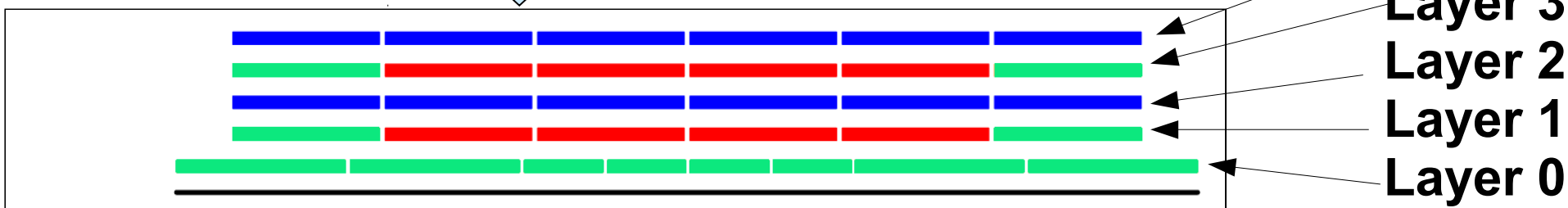
In total, 731,136 readout channels



Double sided barrel



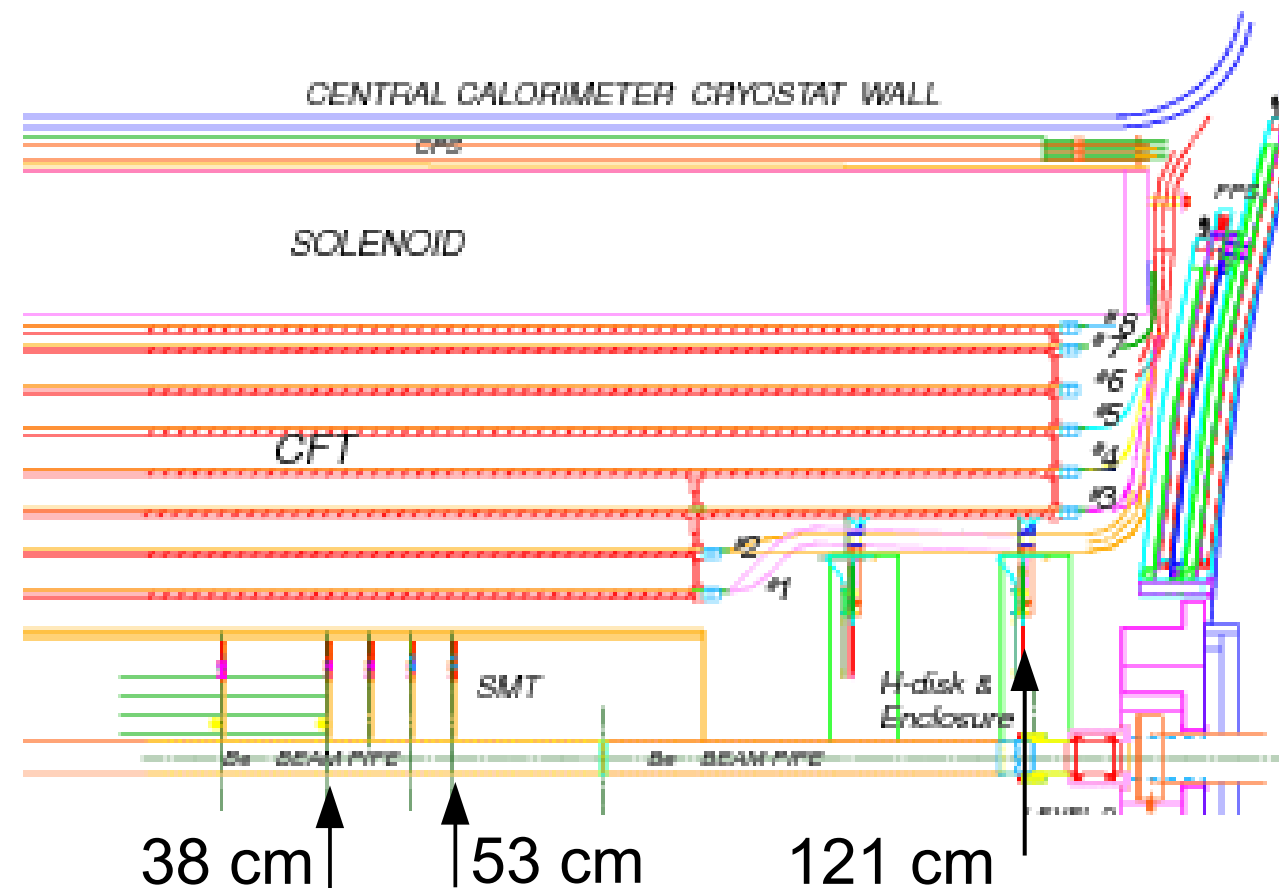
F-disk



r-z view



# The DØ Tracking System

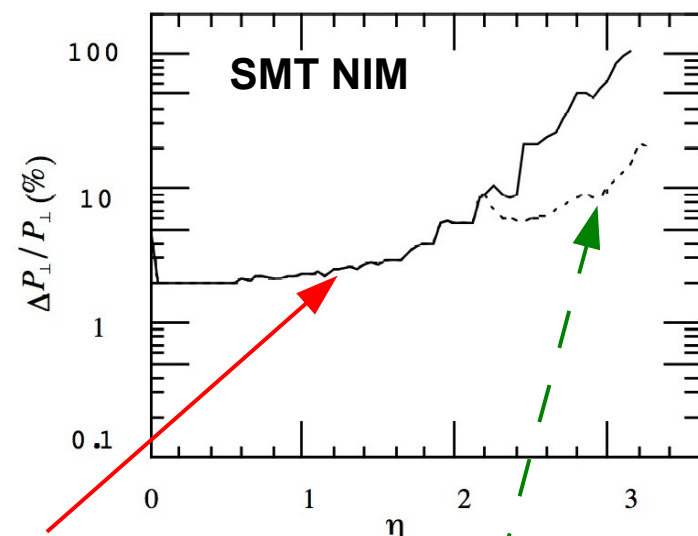


SMT	50 $\mu\text{m}$
CFT	835 $\mu\text{m}$

Strip spacing,  
sometimes larger

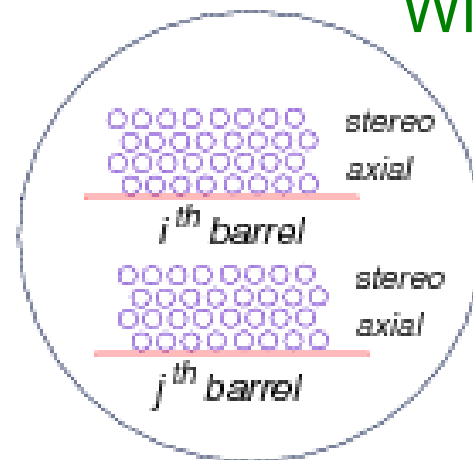
Fiber width

Tracking System Pt Resolution (1 GeV/c Pt track)

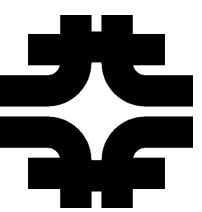


Without H-disks

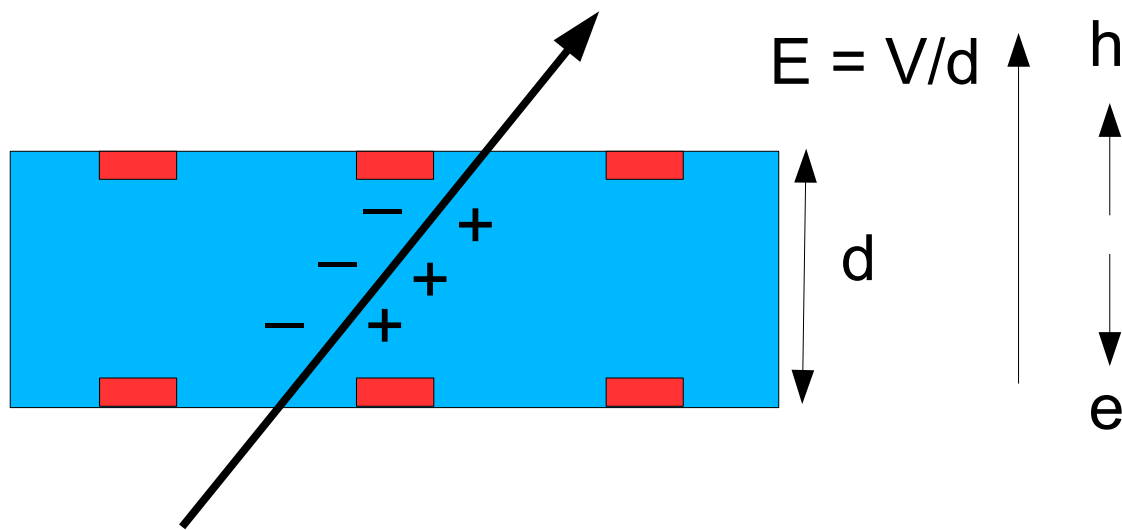
With H-disks



End View (CFT)



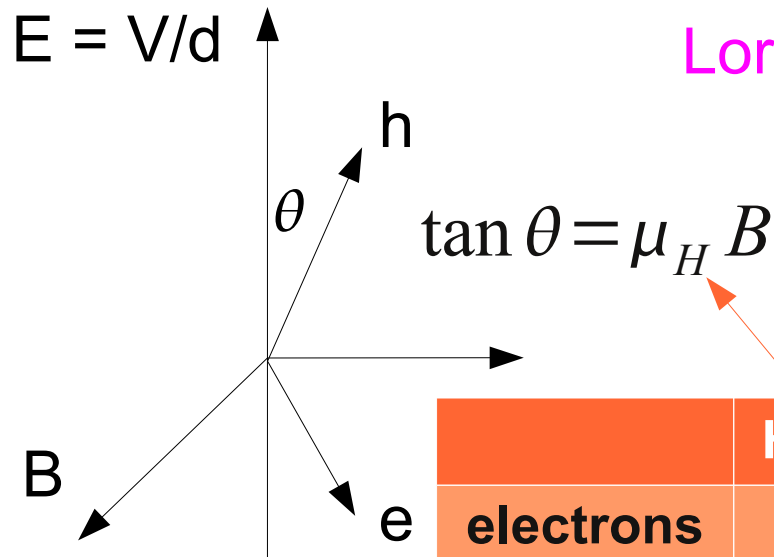
# Lorentz Drifts



Drift velocity

$$v = \mu E = \mu \frac{V}{d}$$

	Mobility (cm <sup>2</sup> /Vs)
electrons	1400
holes	450



Lorentz drift can bias position measurement

Same direction for electrons and holes

	Hall Mobility (cm <sup>2</sup> /Vs)	$\tan \theta$
electrons	1670	0.33
holes	370	0.74